



#72/K
12/31/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
Shunpei YAMAZAKI et al.)
Serial No. 08/691,434)
Filed: August 2, 1996)
For: METHOD OF FABRICATING)
SEMICONDUCTOR DEVICES AND)
APPARATUS FOR PROCESSING A)
SEMICONDUCTOR)

Art Unit: 2822
Examiner: M. Wilczewski

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with
The United States Postal Service with sufficient postage as First
Class Mail in an envelope addressed to: Commissioner for Patents,
Washington, D.C. 20231, on 12/13/02

PRELIMINARY AMENDMENT

Honorable Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated August 13, 2002 please amend the above-
identified application as follows:

IN THE CLAIMS:

Please cancel claims 76-77, 79, 84-85 and 90-91 and amend claims 16, 56, and 74-
75 as follows:

16. (Amended) An apparatus for processing a semiconductor comprising:
- a first vacuum chamber;
 - an ion introducing apparatus for doping a semiconductor layer formed over a substrate with a dopant impurity through an insulating film comprising oxide provided over said semiconductor layer;
 - an etching apparatus for etching said insulating film comprising oxide to expose a surface of said semiconductor layer, said etching apparatus connected to said ion introducing apparatus through said first vacuum chamber;

29

K